

LIQUID RECOVERY APPARATUS, EXPOSURE APPARATUS, EXPOSURE METHOD, AND DEVICE MANUFACTURING METHOD

Abstract

An exposure apparatus exposes a substrate by projecting an image of a pattern onto the substrate via a projection optical system and a liquid that fills a gap between the projection optical system and the substrate. The exposure apparatus has a liquid recovery mechanism with a drive section powered by electric power supplied from a commercial power source and an uninterruptible power source separate from the commercial power source. When the commercial power source has a failure, the supply of electric power to the drive section is switched to the uninterruptible power source.

Figure 1